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(54) Title: SYSTEM AND METHOD FOR DYNAMIC ABERRATION CORRECTION

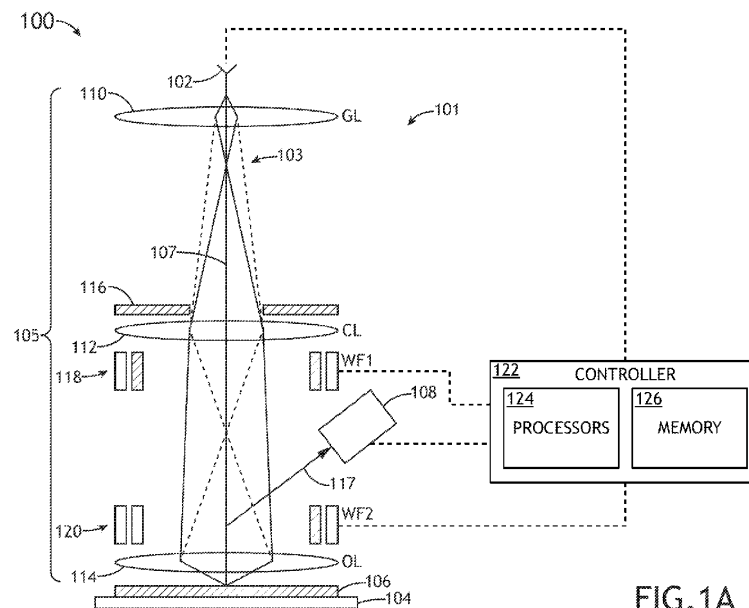


FIG. 1A

(57) Abstract: A method for dynamic aberration correction includes generating a primary electron beam with an electron beam source. The method includes directing the primary electron beams to a sample with an electron-optical column and deflecting the primary electron beam to an objective lens of the electron-optical column using a first Wien filter to correct for coma blur in the primary electron beam. The method includes generating off-axis chromatic aberration in the primary electron beam using the objective lens. The method includes adjusting one of a strength or orientation of the Wien filter to correct the off-axis chromatic aberration in the primary electron beam generated by the objective lens. The method includes detecting one or more secondary electrons emanating from the sample.

[Continued on next page]

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